

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	6943	polysilicon and (SiO ₂ ?sub?xN?xub?y or silicon near oxynitride or (nitrided near (silicon near (dioxide or oxide))))	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/20 07:23
L2	3	l1 and plasam	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/20 07:23
L3	4979	l1 and plasma	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/20 07:23
L4	319	l3 and processing near chamber	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/20 07:23
S1	160	nitrided near (silicon near oxide or SiO ₂ ?sub?2) and plasma	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 17:07
S2	27	("4621277" "4623912" "4913929" "5445999" "5455204" "5834353" "5861651" "5891809" "5939763" "6013553" "6048769" "6060369" "6060403" "6087236" "6096614" "6184110" "6228779" "6239044" "6245689" "6248628" "6251761" "6265327" "6294819" "6306741" "6548366" "6566205").PN. OR ("6780720"). URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 09:16
S3	91	("4913929").URPN.	USPAT	OR	OFF	2006/01/19 10:08
S4	1	"6265327".pn.	USPAT	OR	OFF	2006/01/19 10:08
S5	31	("4135097" "4147573" "4179312" "4870030" "4929986" "5055696" "5180435" "5334554" "5569499" "5672521" "5716870").PN. OR ("6265327"). URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 11:52
S6	1	"20020197884".pn.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 11:58
S7	0	ep1326271.pn.	EPO; JPO; DERWENT	OR	OFF	2006/01/19 11:59
S8	0	ep1326271	EPO; JPO; DERWENT	OR	OFF	2006/01/19 11:59
S9	0	EP1326271	EPO; JPO; DERWENT	OR	OFF	2006/01/19 12:00
S10	0	EP01326271	EPO; JPO; DERWENT	OR	OFF	2006/01/19 12:01

S11	34	nitrided near silicon near (dioxide or oxide)	EPO; JPO; DERWENT	OR	OFF	2006/01/19 12:00
S12	0	EP0001326271	EPO; JPO; DERWENT	OR	OFF	2006/01/19 12:01
S13	0	EP0001326271.pn.	EPO; JPO; DERWENT	OR	OFF	2006/01/19 12:01
S14	0	"2001049186".pn.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 12:02
S15	7	"1326271"	EPO; JPO; DERWENT	OR	OFF	2006/01/19 12:28
S16	31712	gate near dielectric or insulator same apparatus	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 12:29
S17	430	gate near (dielectric or insulator) same apparatus	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 12:29
S18	3	S17 and nitrided near silicon near (dioxide or oxide)	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 12:30
S19	0	integrated near processing near system]	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 12:30
S20	493	integrated near processing near system	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 12:30
S21	221	S20 and processing near chamber	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 13:08
S22	3	S21 and (silicon near (oxynitride or nitrided)) near silicon near (oxide or dioxide)	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 12:33
S23	2224	S21 vand SiO ₂ xN ₂ y	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 12:33
S24	6	S21 and SiO ₂ xN ₂ y	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 12:33
S25	0	"2001049186".pn.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 13:09
S26	1	"20010049186".pn.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 13:11
S27	2	"06140392".pn.	EPO; JPO; DERWENT	OR	OFF	2006/01/19 15:09

S28	7777	gate near insulator	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 15:10
S29	23154	S28 processing near chamber	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 15:11
S30	111	S28 and processing near chamber	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 15:11
S31	14	("5413664" "5529630" "5578520" "5648276" "5811328" "5840118" "5851860" "5953595" "5956581" "6063654" "6080643" "6348369" "6444506").PN. OR ("6673126"). URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 15:14
S32	43	("5578520").URPN.	USPAT	OR	OFF	2006/01/19 15:23
S33	14	("6329229").URPN.	USPAT	OR	OFF	2006/01/19 15:28
S34	211	multi near chamber and silicon near oxynitride	USPAT	OR	OFF	2006/01/19 15:28
S35	218	nitrided near (silicon near oxide or SiO ₂) and (heat\$3 or anneal\$3)	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 17:08
S36	44	nitrided near (silicon near oxide or SiO ₂) and ((heat\$3 or anneal\$3)same ammonia)	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/19 17:09
S37	65	("5397720" "5403786").URPN.	USPAT	OR	OFF	2006/01/19 17:14